

IN THE CLAIMS

The following listing of the claims is provided in accordance with 37 C.F.R.
1.121:

1. (original) A delivery device for a thin film deposition or etching apparatus, comprising:
a heated gas inlet line for delivering a gas to a powered electrode of the apparatus, the gas inlet line maintained under a vacuum; and
a coupling device located between the powered electrode and the gas inlet line, the coupling device comprising insulation portion.
2. (original) The device of claim 1, wherein the gas inlet line is directly connected to the coupling device.
3. (original) The device of claim 2, wherein the coupling device is directly connected to the powered electrode.
4. (original) The device of claim 1, wherein the thin film deposition or etching apparatus comprises a PECVD apparatus.
5. (original) The device of claim 1, wherein the insulation portion is both thermally and electrically insulating.
6. (original) The device of claim 1, wherein the insulation portion comprises a plastic or a ceramic material.
7. (original) The device of claim 3, wherein the coupling device further comprises a flange for maintaining the gas inlet line under a vacuum.

8. (original) The device of claim 7, wherein the flange is connected to the gas inlet line, the insulation portion is connected to the powered electrode, and the insulation portion and flange are connected to each other.

9. (original) A delivery device for delivering a gas to a thin film deposition or etching apparatus, the system comprising:
a heated gas inlet line maintained under a vacuum; and
a coupling device located between a powered electrode of the apparatus and the gas inlet line, the coupling device comprising thermal and electrical insulation portion.

10. (original) The device of claim 9, wherein the gas inlet line is directly connected to the coupling device.

11. (original) The device of claim 10, wherein the coupling device is directly connected to the powered electrode.

12. (original) The device of claim 9, wherein the electrical insulation portion comprises a plastic or a ceramic material.

13. (original) The device of claim 11, wherein the coupling device further comprises a flange for maintaining the gas inlet line under a vacuum.

14. (original) The device of claim 13, wherein the flange is connected to the gas inlet line, the insulation portion is connected to the powered electrode, and the insulation portion and flange are connected to each other.

15. (original) A PECVD apparatus containing a delivery system, the system comprising:
a heated gas inlet line maintained under a vacuum; and

a coupling device located between a powered electrode of the PECVD apparatus and the gas inlet line, the coupling device comprising insulation portion and flange device for maintaining the gas inlet line under a vacuum.

16. (original) The device of claim 15, wherein the gas inlet line is directly connected to the coupling device and the coupling device is directly connected to the powered electrode.

17. (original) The device of claim 15, wherein the insulation portion is both thermally and electrically insulating.

18. (original) The device of claim 16, wherein the flange is connected to the gas inlet line, the insulation portion is connected to the powered electrode, and the insulation portion and flange are connected to each other.

19.-31. (canceled).